4. (Original) An antireflection film-forming composition comprising the polymer of Claim 3 and a solvent.

5. (Currently Amended) [[The]] An antireflection film-forming composition comprising, a polymer having a structural unit of the following formula (4)

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
R^5 & H \\
\hline
C & C \\
C & C \\
\hline
C & C \\
C & C \\
\hline
C & C \\
C & C$$

wherein R4 is a hydrogen atom or a monovalent organic group selected from the group consisting of a phenyl group, an alkyl group, an alkenyl group, an acyl group, and a group in which one or more hydrogen atoms of a phenyl group, an alkyl group, an alkenyl group, or an acyl group are replaced by one or more of the same or different substituents selected from the group consisting of a halogen atom, a hydroxyl group, a mercapto group, a nitro group and a sulfonic acid group, R<sup>5</sup> is a monovalent atom or a monovalent organic group, and n is 0 or 1, and a solvent.

6. (Currently Amended) An antireflection film-forming composition comprising, at least one polymer selected from the group consisting of: a polymer having [[the]] a structural unit of the following formula (3) of Claim 3

$$\begin{array}{c|c}
R^6 & R^7 \\
\hline
C & C
\end{array}$$
(5)

wherein R<sup>6</sup> and R<sup>7</sup> individually represent a monovalent atom or a monovalent organic group[[,]]; and a polymer having a structural unit of the formula (4) and a structural unit of the formula (5); and

a solvent.

- 7. (Original) The antireflection film-forming composition according to Claim 4, further comprising an acid generator.
- 8. (Original) The antireflection film-forming composition according to Claim 5, further comprising an acid generator.
- 9. (Original) The antireflection film-forming composition according to Claim 6, further comprising an acid generator.
  - 10. Canceled
  - 11. (New) An antireflection film-forming composition comprising: a polymer having a structural unit of the following formula (4):

$$\begin{array}{c|c}
 & H \\
 & C \\
 & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
 & C \\
 & C \\
 & H
\end{array}$$

$$\begin{array}{c|c}
 & C \\
 & C$$

wherein R<sup>4</sup> is a hydrogen atom or a monovalent organic group and R<sup>5</sup> is a monovalent atom or a monovalent organic group; and

a solvent.

12. (New) The antireflection film-forming composition according to Claim 11, further comprising an acid generator.